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Section  
#5 08/06/03*  
XA-9613

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Toshihiko TANAKA et al.

Appln. No.: 10/045,036

Group Art Unit: 3729

Filed: January 15, 2002

Examiner: Thiem Phan

For: WIRING SUBSTRATE MANUFACTURING METHOD

\* \* \*

RESPONSE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

Sir:

In response to the Office Action mailed July 1, 2003,  
and to the requirement for restriction therein, Applicants  
elect Group I (Claims 1-8) with traverse.

Applicants assert that the requirement for restriction  
is inappropriate, because the subject matter of all of the  
claims relates to the "wiring substrate manufacturing  
method". More particularly, a main feature of Claim 9 (the

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use of "a photomask which has a shade pattern containing at least nano particles and a binder") is common to Claim 1.

Similarly, Claim 12 recites the use of "a photomask having a shade pattern", which is common to Claim 1.

Applicants reserve the right to file a divisional application with regard to any subject matter which might be considered non-elected.

The Commissioner is hereby authorized to charge to Deposit Account No. 50-1165 any fees under 37 C.F.R. §§ 1.16 and 1.17 that may be required by this paper and to credit any overpayment to that Account. If any extension of time is required in connection with the filing of this paper and has not been requested separately, such extension is hereby requested.

Respectfully submitted,

NHS:lmb

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By: Nelson H. Shapiro  
Nelson H. Shapiro  
Reg. No. 17,095

July 30, 2003